

# Week 14

## Thin Film Transistors 2

Ambipolar and Other Transistor Architectures

Morphology

Reliability

Applications

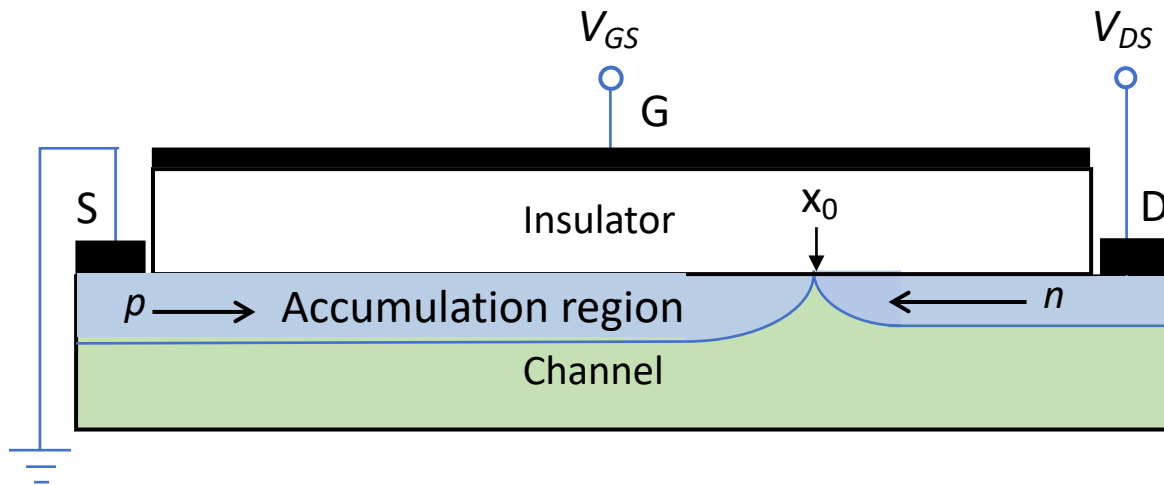
Chapter 8.3.2-8.4, 8.6-8.9



Organic Electronics  
Stephen R. Forrest

# Ambipolar OTFTs

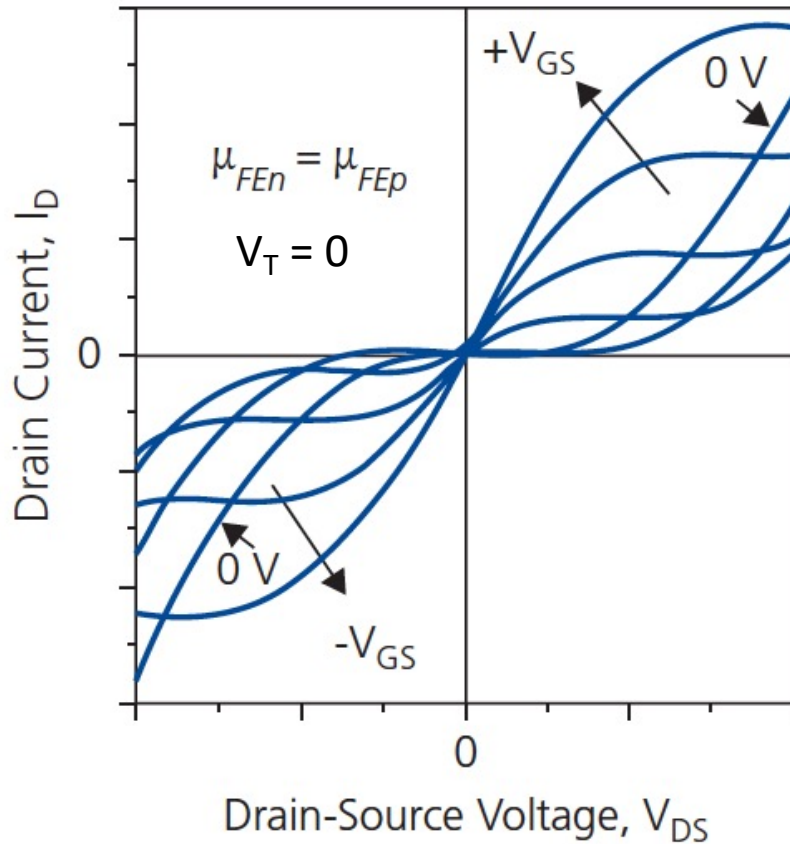
- Channel capable of supporting both electron and hole transport
- Advantage: Complementary logic possible with a single structure



Strategies for achieving bipolar action:

- Use material with both high  $\mu_{FEn}$  and  $\mu_{FEp}$  with contacts in the middle of the energy gap (i.e. use ambipolar conducting organics)
- Use a bilayer, one with higher electron vs. hole mobility and vice versa
- Use a blend of electron and hole transporting materials

# Ambipolar transfer characteristics



Example:  $V_{Tp} < V_{Tn}$

Linear regime

$$I_D = \frac{WC_i}{L} \mu_{FEn} \left( V_{GS} - V_{Tn} - \frac{V_{DS}}{2} \right) V_{DS}$$

$$\left( \begin{array}{l} 0 \leq V_{DS} \leq V_{DSsat} \\ V_{GS} > V_{Tn} \end{array} \right)$$

Saturation regime

$$I_D = \frac{WC_i}{2L} \mu_{FEn} (V_{GS} - V_{Tn})^2$$

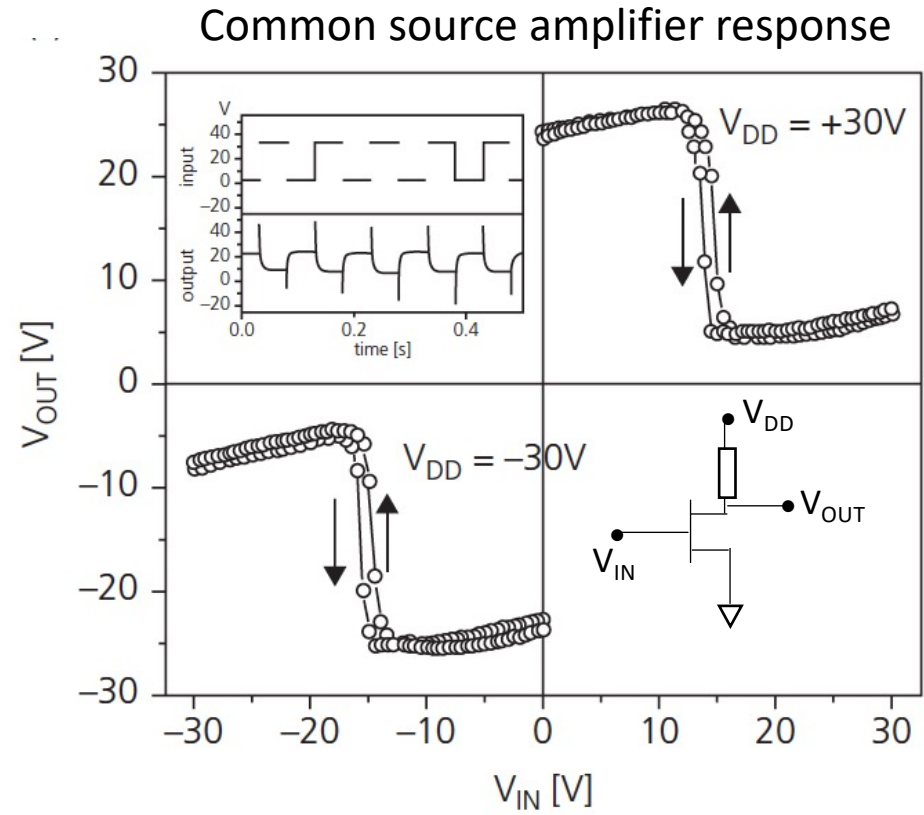
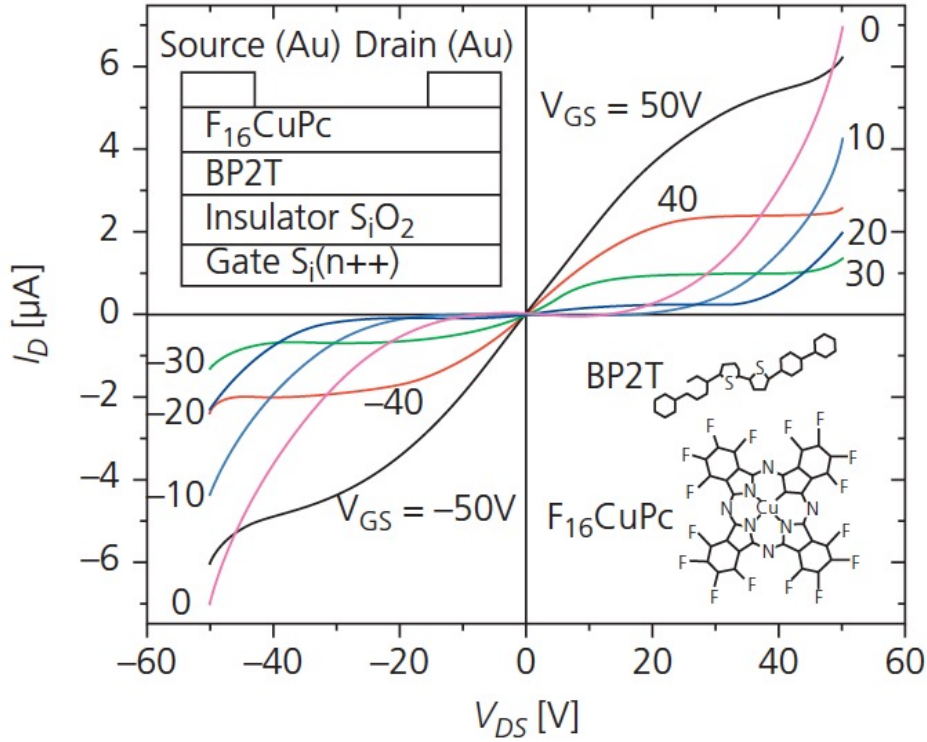
$$\left( \begin{array}{l} V_{DS} \geq V_{GS} - V_{Tn} \\ V_{DS} \leq V_{GS} - V_{Tp} \end{array} \right)$$

Ambipolar (quadratic) regime

$$I_D = \frac{WC_i}{2L} \left\{ \mu_{FEn} (V_{GS} - V_{Tn})^2 + \mu_{FEp} (V_{DS} - V_{GS} + V_{Tp})^2 \right\}$$

$$V_{DS} \geq V_{GS} - V_{Tp} \geq V_{GS} - V_{Tn}$$

# Bilayer ambipolar OTFT

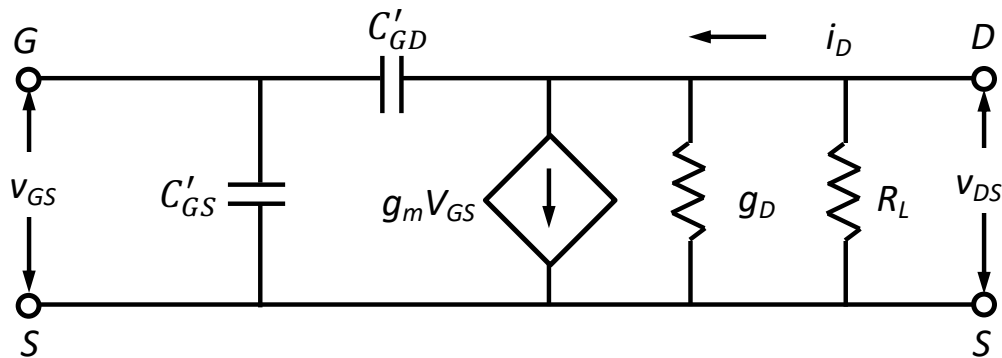


Disadvantage of the ambipolar OTFT:  $I_{on}/I_{off}$  is small since no condition where one carrier type is completely absent.



# OTFT Bandwidth

Small signal equivalent circuit



$C_{GS}'$  = total gate-source capacitance (including parasitics)

$C_{GD}'$  = total gate-drain capacitance

$R_L$  = external load resistance

Small signal input (gate) current:  $i_{GS} = WLC_G \left. \frac{\partial v_{GS}}{\partial t} \right|_{V_{DS}} = j\omega (WLC_G) v_{GS} = j2\pi f (WLC_G) v_{GS}$

Small signal output (drain) current:  $i_D \approx g_m v_{GS}$

The maximum transistor bandwidth is reached when the current gain  $\left| \frac{i_D}{i_G} \right| = 1$

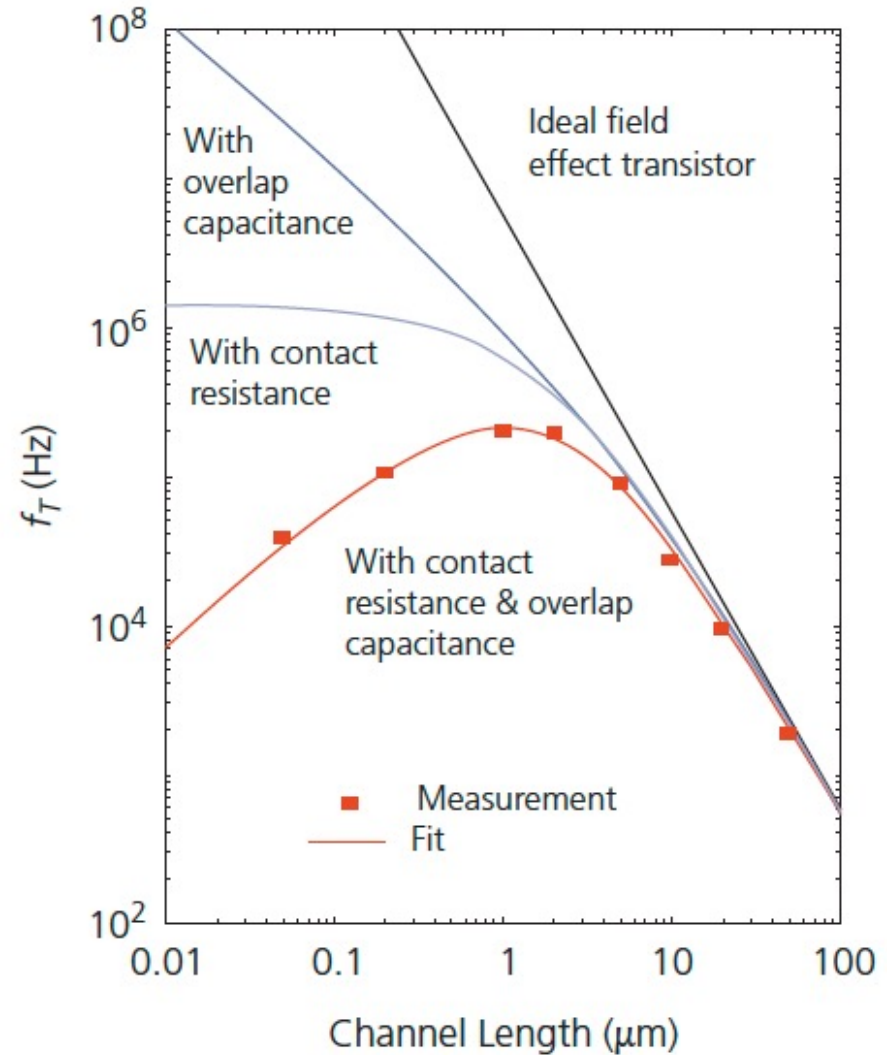
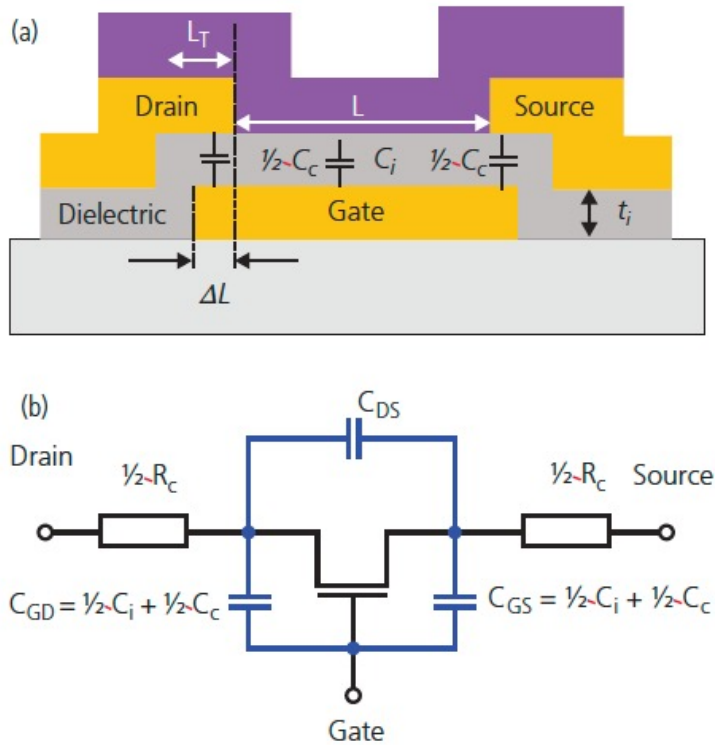
From these expressions, we get the cutoff, or transfer frequency:

$$f_T = \frac{g_m}{2\pi WLC_G} \Rightarrow \frac{g_m}{2\pi WL(C_{GS} + C_M)}$$

$C_M$  = Miller capacitance

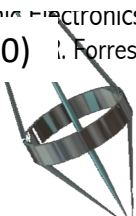
# Contact Resistance Limits OTFT Performance

Sources of Parasitic Resistance and Capacitance



Hoppe, et al., Organic Electron., 11, 626 (2010) J. Forrest

$$R_C = r_S + r_D$$



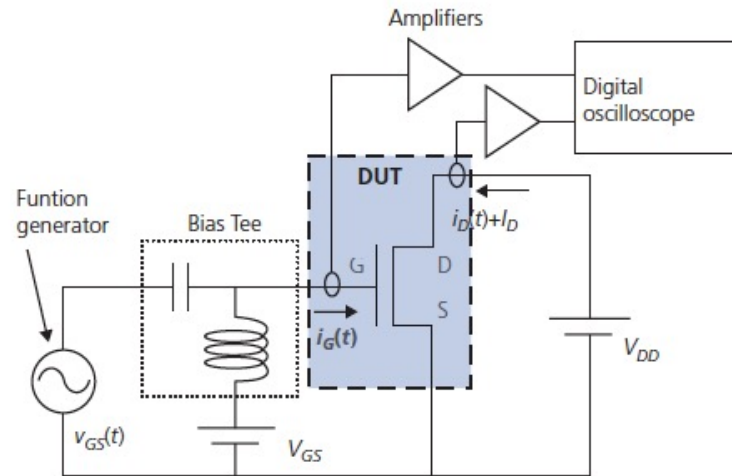
This leads to corrected transconductance and output conductance...

$$g'_m = \frac{g_m}{1 + r_S g_m} \quad g'_D = \frac{g_D}{1 + (r_S + r_D) g_D}$$

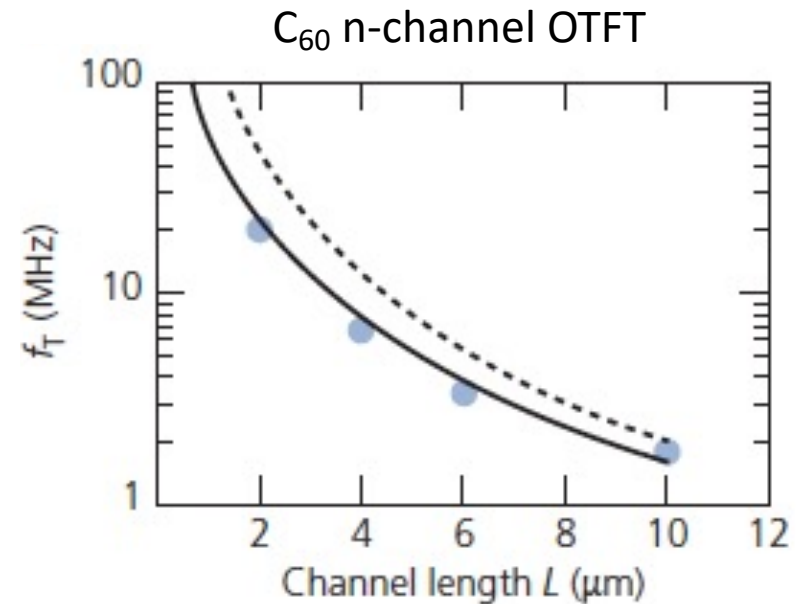
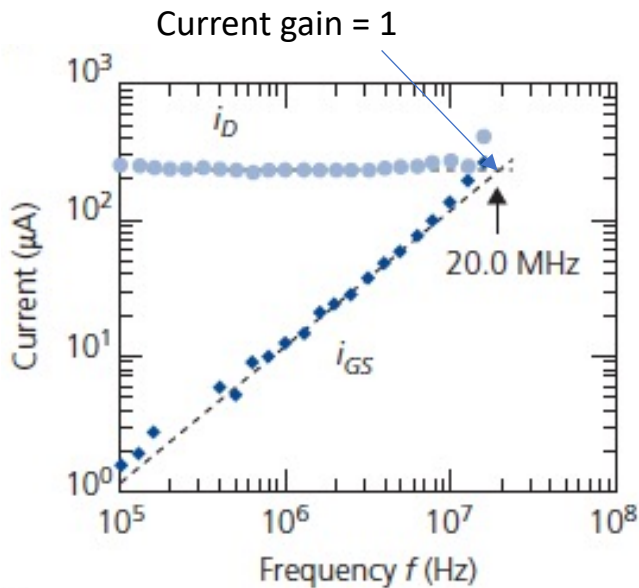
... and frequency response

$$f_T = \frac{\mu_{FE0} (V_{GS} - V_T)}{2\pi L (L + \Delta L)} \left[ \frac{1}{1 + W \mu_{FE0} C_G (V_{GS} - V_T) R_C / L} \right]$$

# Example: High Bandwidth OTFT



Frequency test circuit



# Performance has come a long way

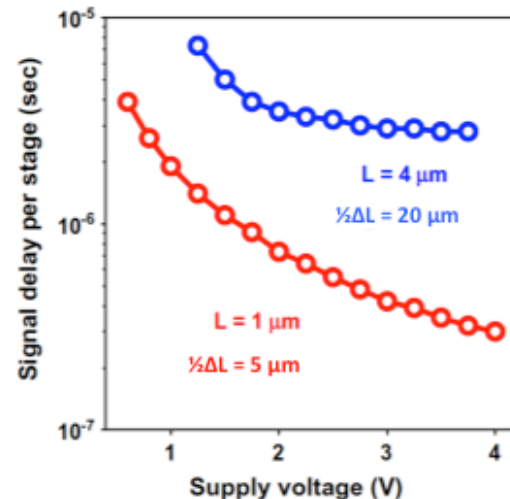


7 stage ring oscillator

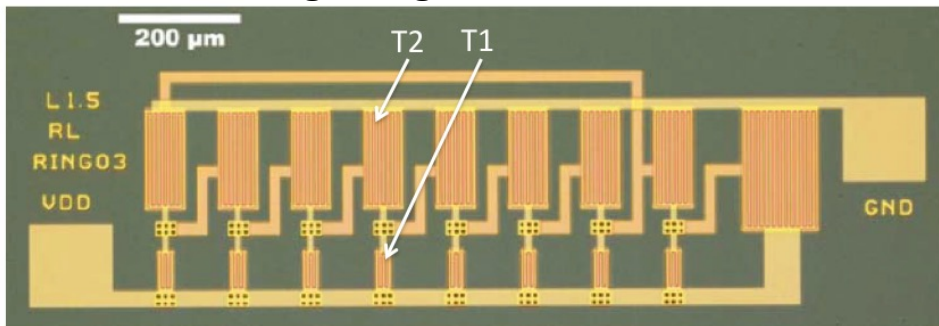
Oscillation frequency  
a function of the  
delay per gate

$$2f_{osc} = 1/N\tau_{delay}$$

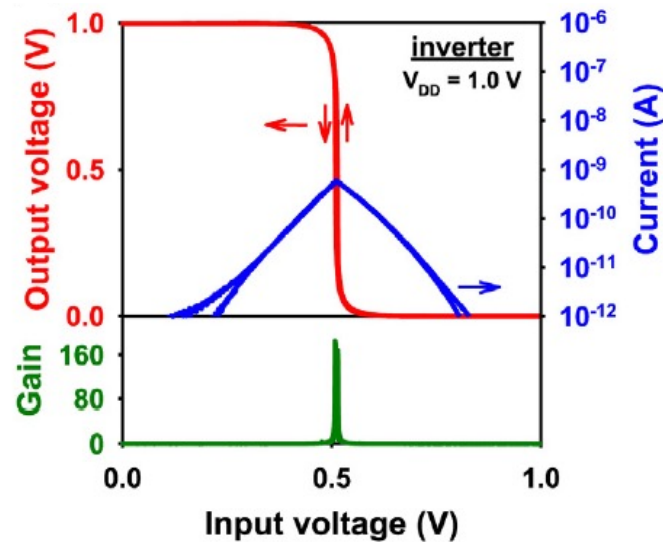
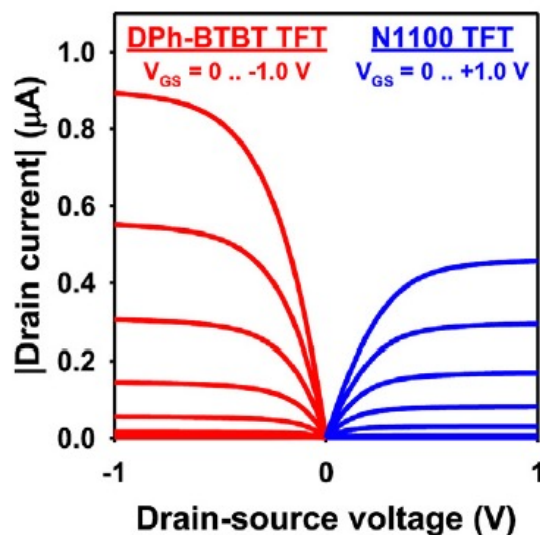
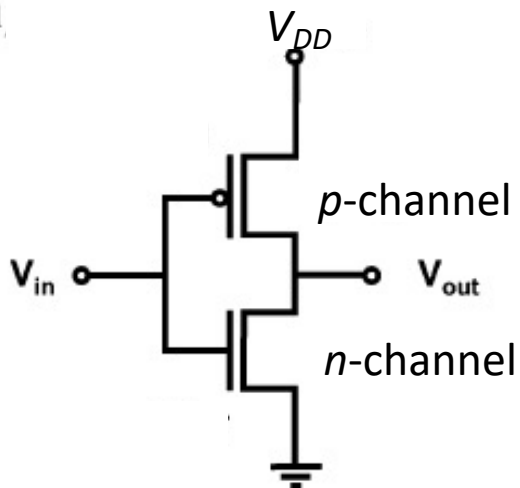
$$f_{delay} = (2\tau_{delay})^{-1} < f_T$$



Zschieschang, et al., 2013.  
*Organic Electronics*, 14, 1516.



Smith et al., *Appl. Phys. Lett.*, 93, 253301 (2008)



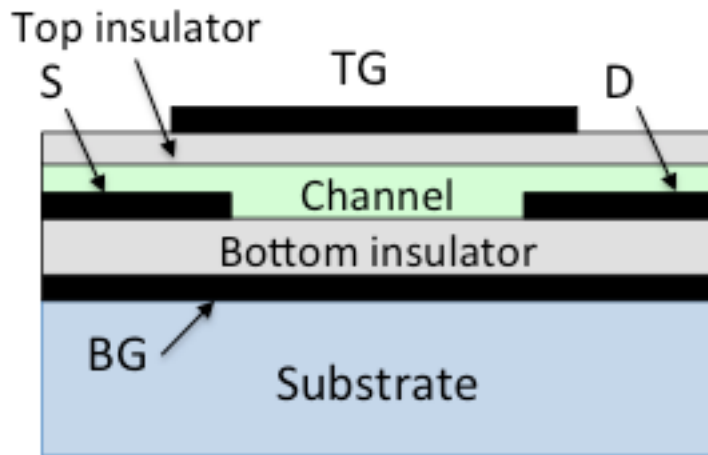
Zschieschang, et al., 2017. *Organic Electronics*, 49, 179.





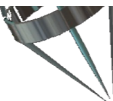
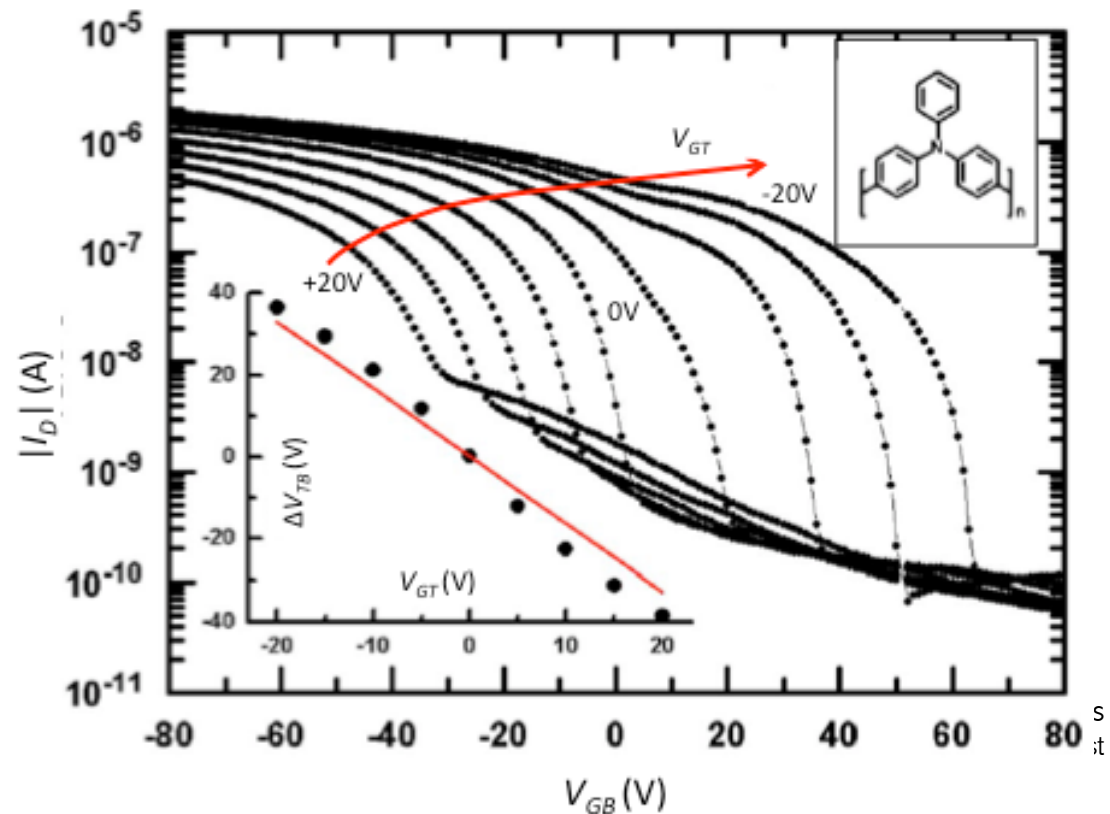
# Dual gate transistors

- Useful for adjusting  $V_T$  due to extra bias control of the second (bottom) gate
- In conventional CMOS technology, this is the “body potential”
- Important for controlling large ICs

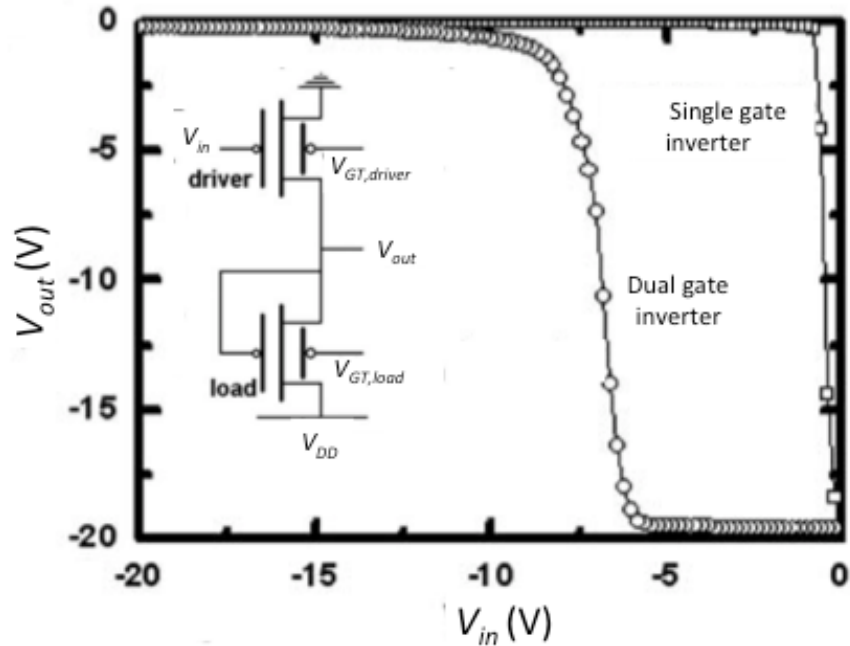


Shift in top gate threshold related to bottom gate voltage:

$$\Delta V_{TT} = \frac{C_B}{C_T} V_{GB}$$



# Dual gate control

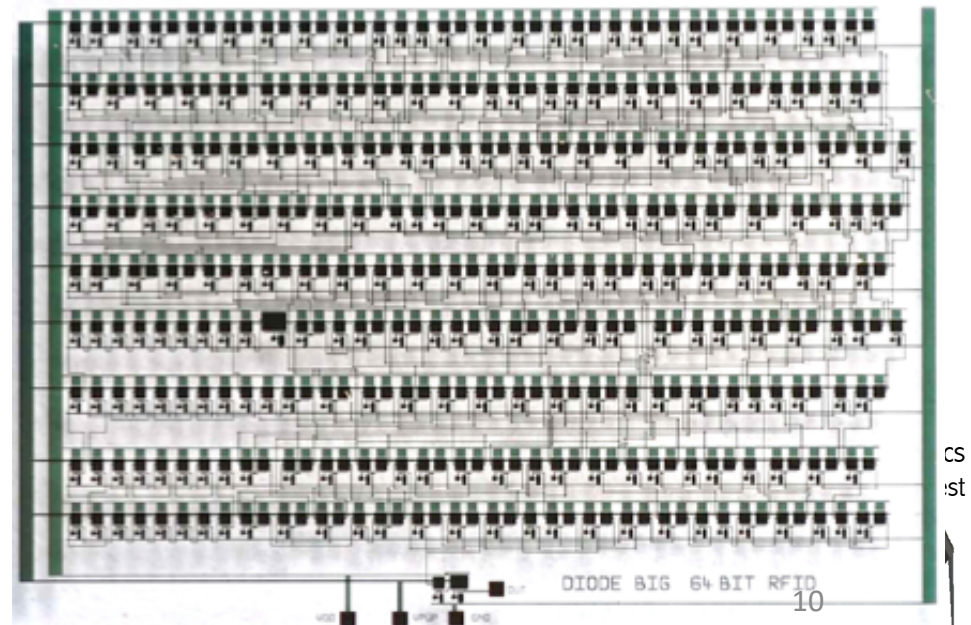


Improved noise margin  
Control of circuit gain

Spijkman et al. Appl. Phys. Lett., 92 143304 (2008)

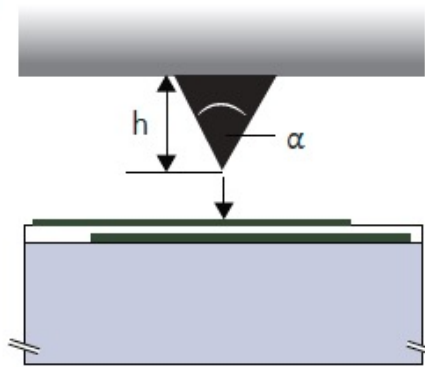
Photograph of a 64-bit RFID transponder operating at 4.3 kb/s using dual gate inverter logic.

Myny et al. IEEE J. Sol. State Circuits, 46, 1223 (2011)

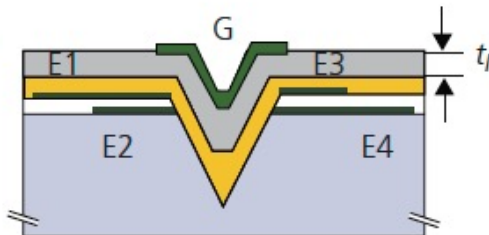
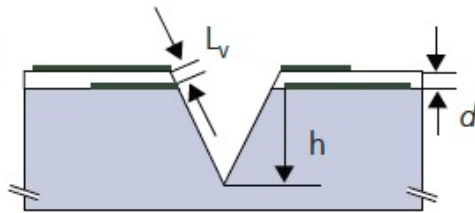


# Other Device Types

## V-gate transistor



Knife edge cuts through contact layers



Channel and gate insulator deposited

Vertical geometries reduce channel transit times  $\Rightarrow$  higher bandwidth

Can be more compact than lateral OTFTs

Can run in vertical mode ( $S=E_1$ ,  $D=E_2$ ) or horizontal mode ( $S=E_1$ ,  $D=E_3$ )

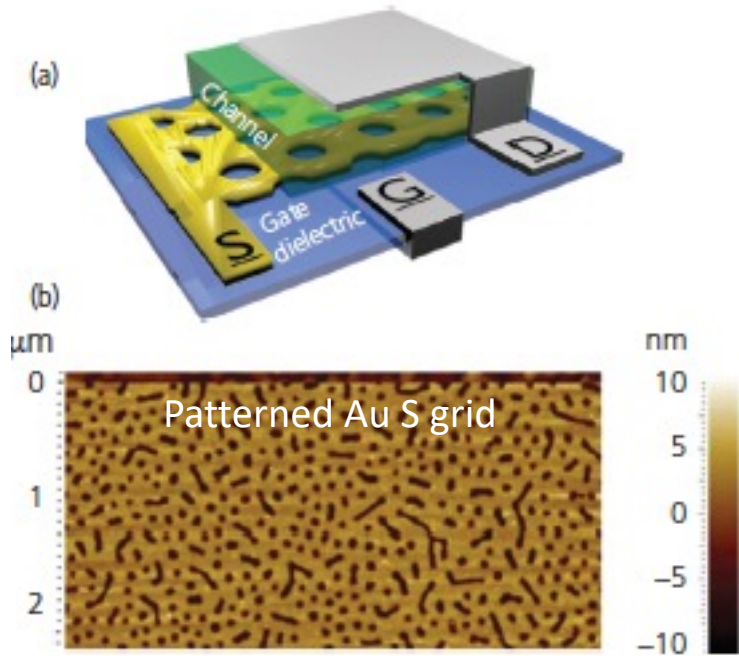
Stutzman, et al., Science, 299, 1881 (2003)



# Other Device Types

## Permeable gate transistor

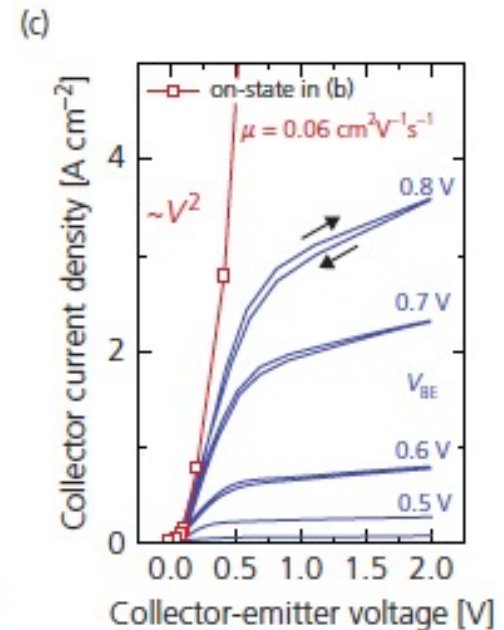
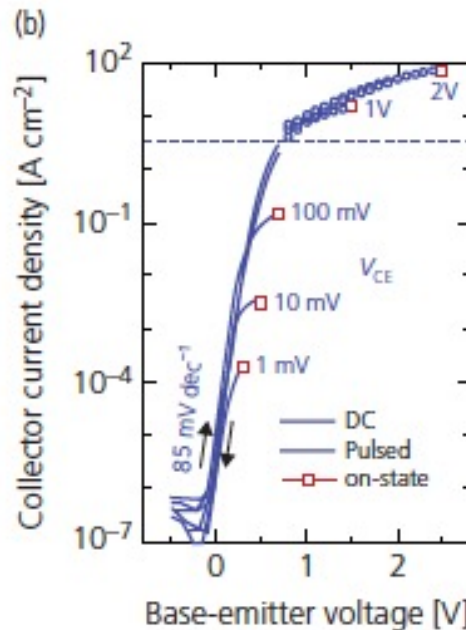
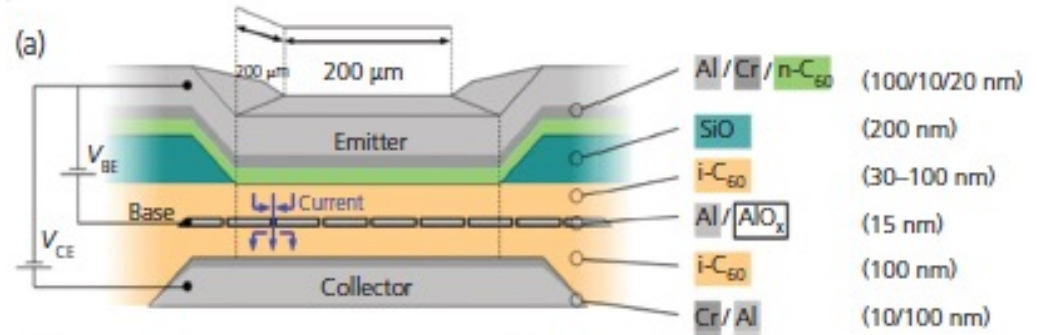
Permeable source V-FET



Gate (removed from S by gate dielectric) controls S-D current by attraction or repulsion of charge

Ben-Sasson et al., (2009). Appl. Phys. Lett., 95, 302.

Permeable Base transistor

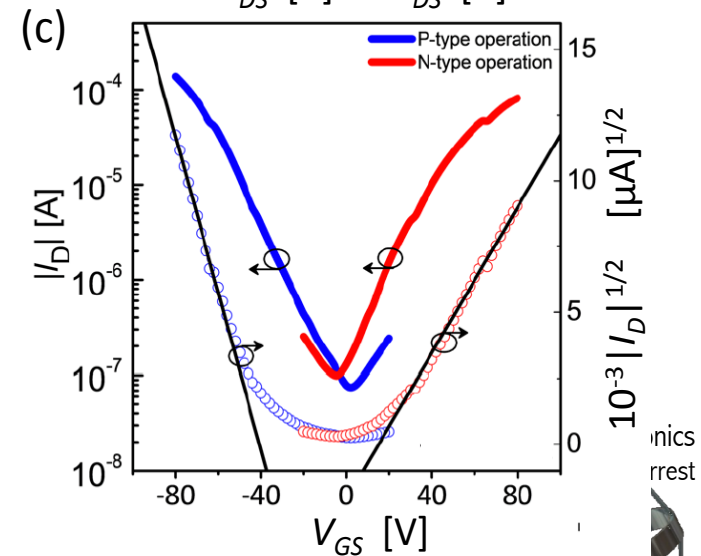
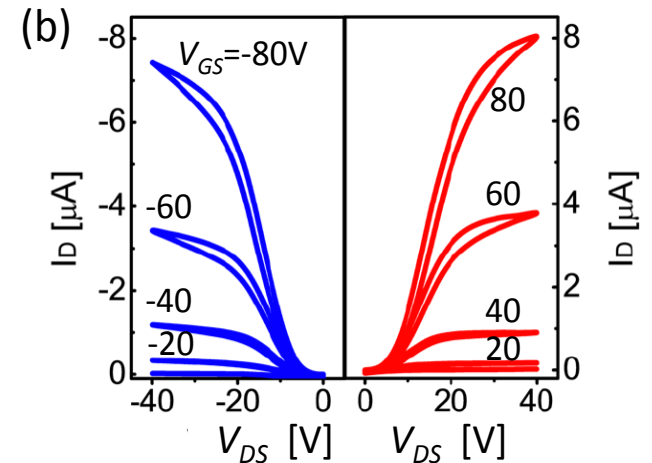
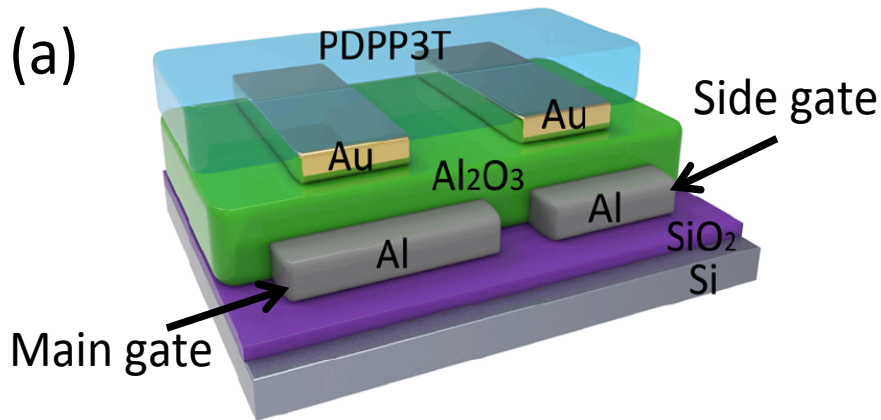


Klinger et al. (2017). Scientific Reports, 7, 44713.

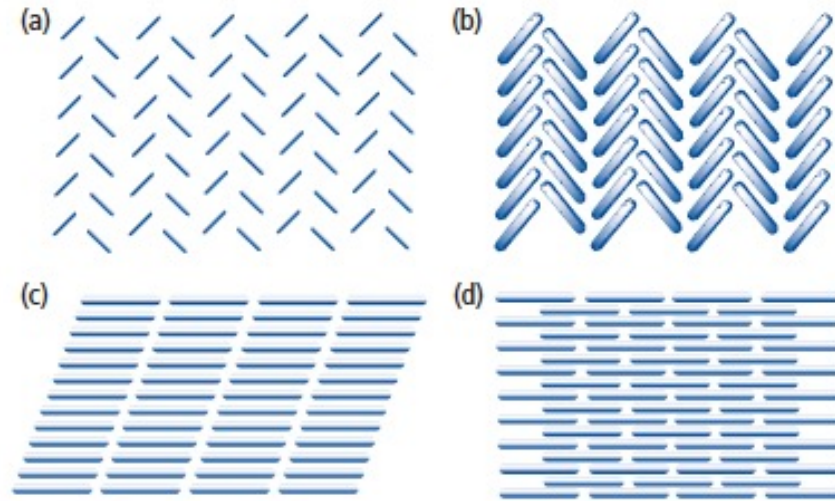
# Other Device Types

## Split gate transistor

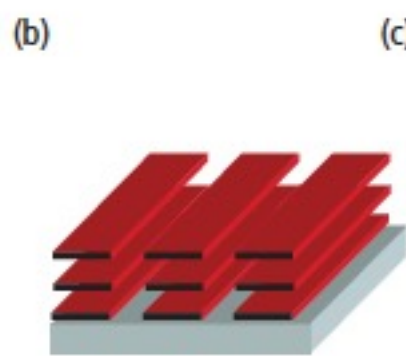
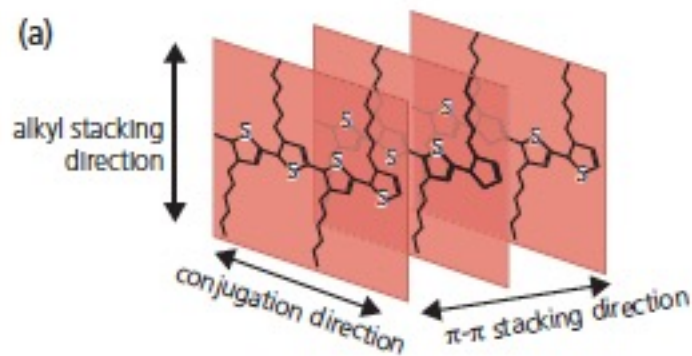
- When gates shorted: ambipolar
- Otherwise, operated as p or n-channel



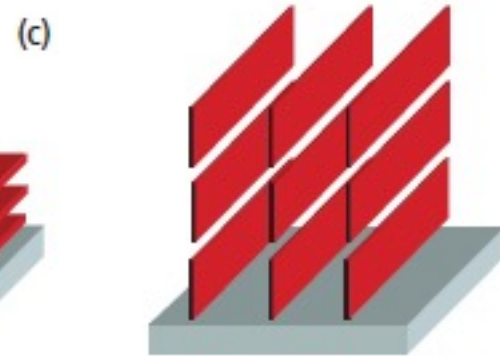
# Highest mobilities when $\pi$ -stacking is in the transistor plane



Different, common organic stacking motifs  
(see Chapter 2)



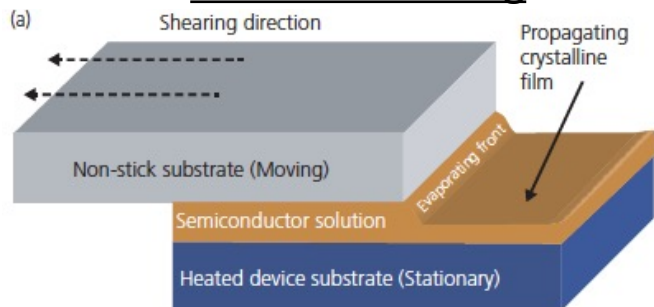
best vertical  
conduction



best in-plane  
conduction

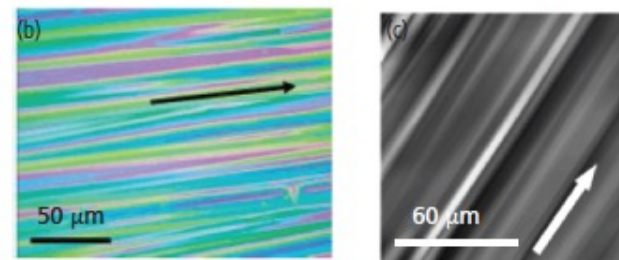
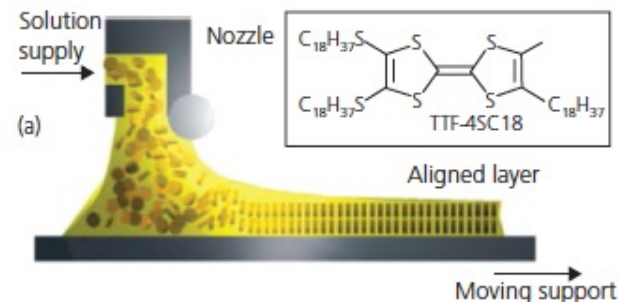
# Methods for Orienting the Channel Semiconductor

## solution shearing



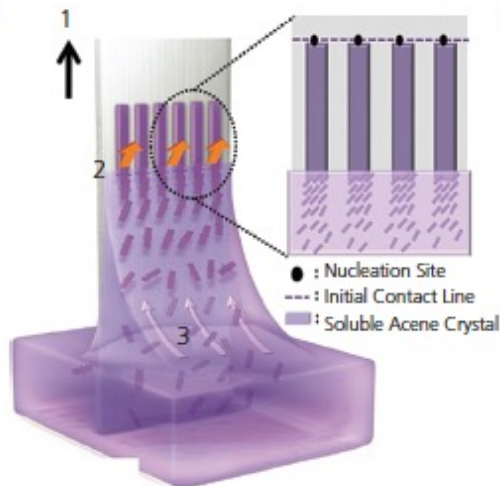
Liu, et al., Z. (2009) Adv. Materials, 21, 1217

## zone casting

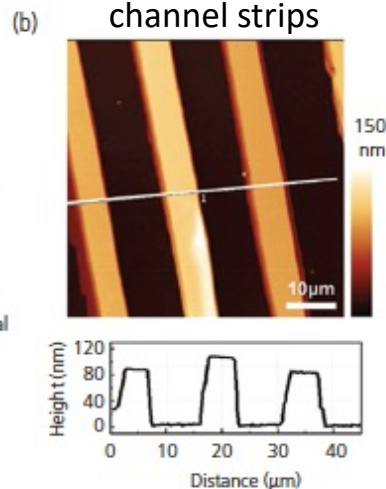


Miskiewicz, et al. (2006). Chem. Materials, 18, 4724.

## dip coating



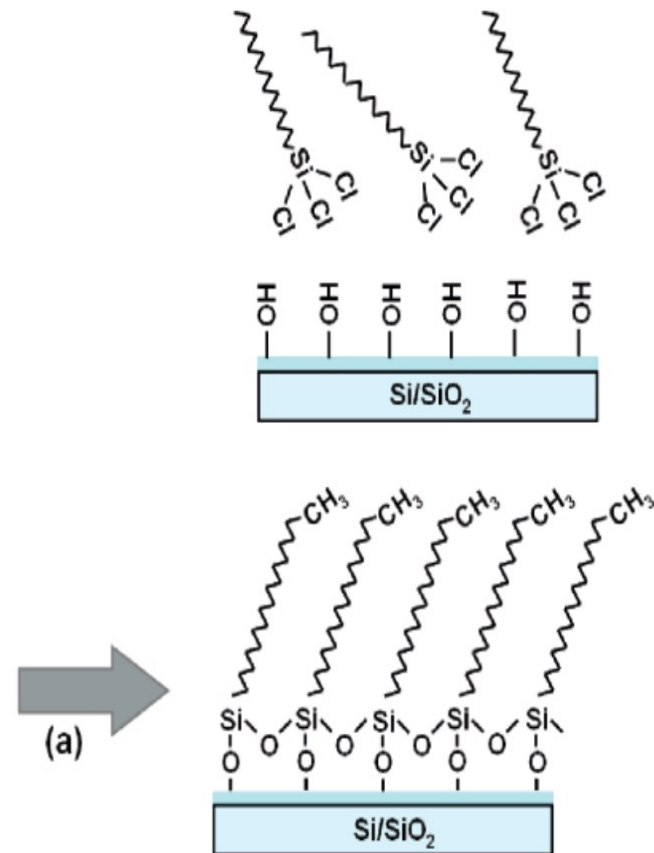
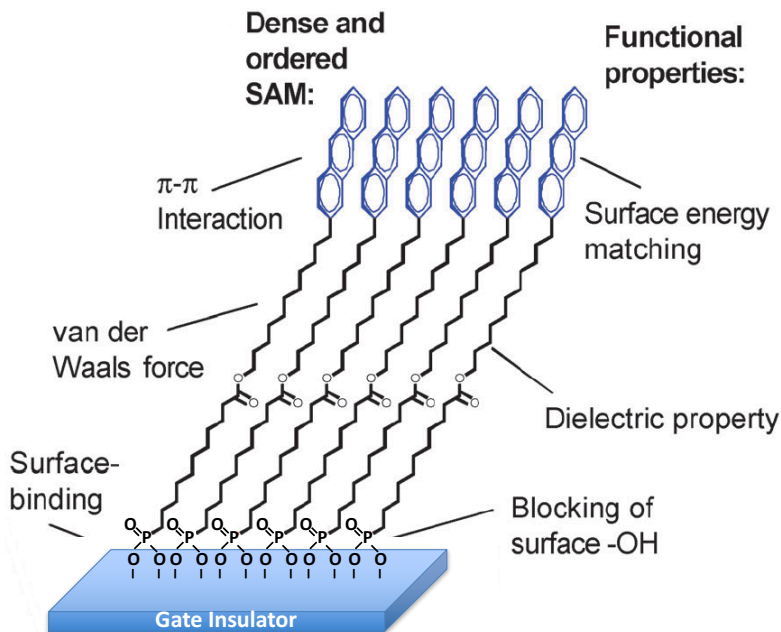
## TIPS-pentacene channel strips



Jang et al., (2012) Adv. Functional Materials, 22, 1005

# Achieving Optimal Morphologies

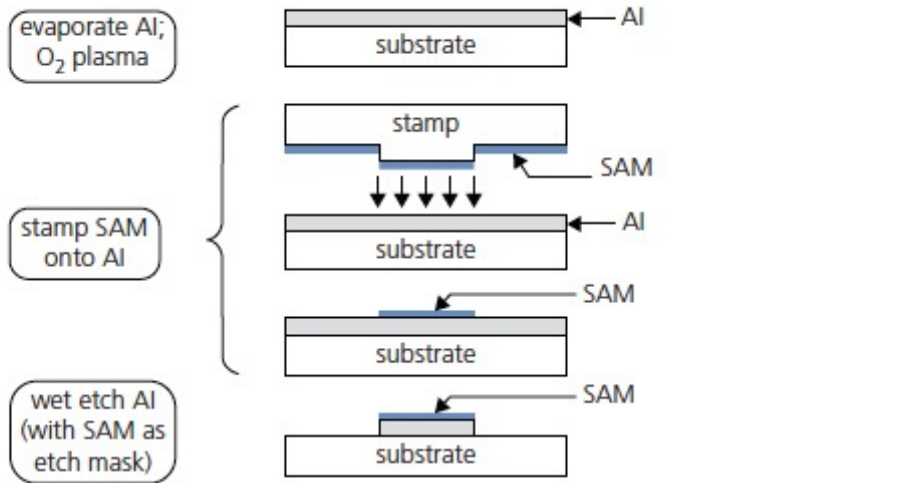
- Method 1: Control during growth by VTE, OVPD, solution
- Method 2: Use Self Assembled Monolayer (SAM) functionalization to initiate growth of desired structures by vapor or solution deposition



Example: Octyltrichlorosilane (OTS)<sup>16</sup>



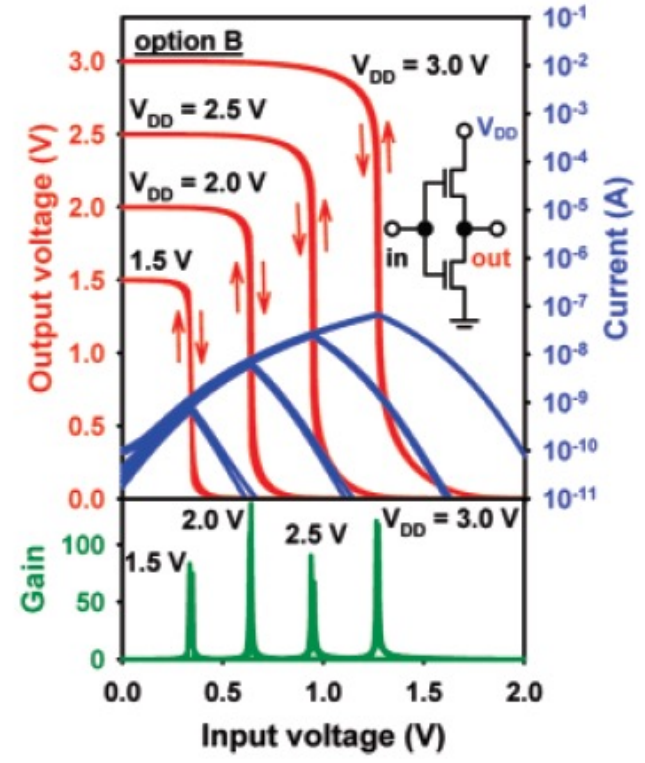
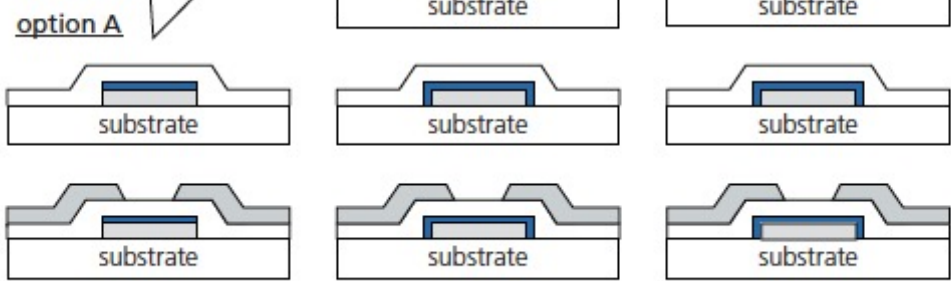
# Contact Printing Initiated by SAM



• improve SAM coverage by dipping the substrate in a solution with molecules

• remove SAM (O<sub>2</sub> plasma)  
• create new SAM (dip)

**option C**

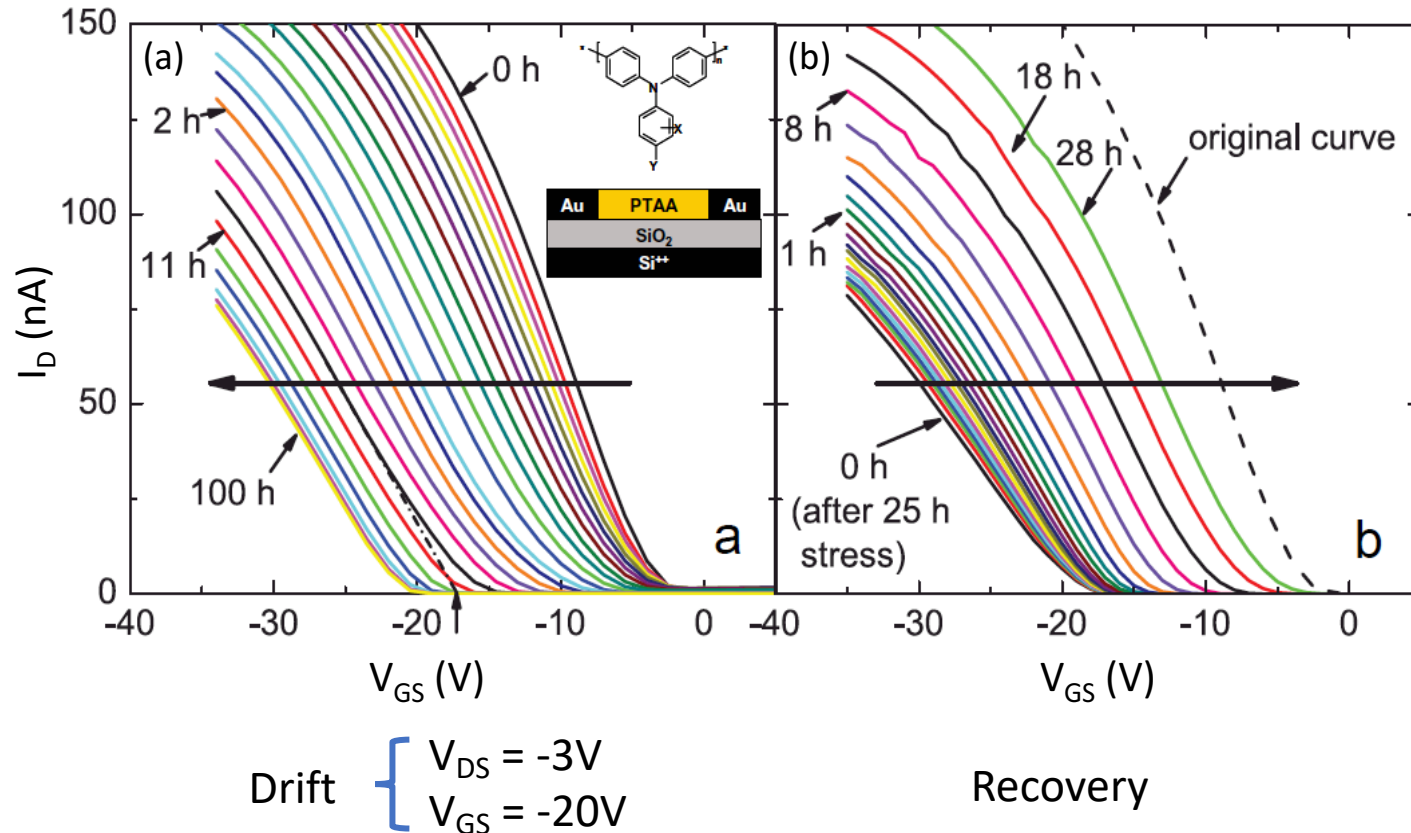


Pentacene (p)  
F<sub>16</sub>CuPc (n)

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# Reliability

- Threshold voltage drift the primary source of circuit failure
  - Decreasing noise margin
  - Increasing leakage



Original transfer characteristics (and  $V_T$ ) partially recovered following stress

# Threshold voltage drift over time

(see Ch. 6.7 & 7.8)

- Drift due to charges migrating in insulator or channel toward the interface
  - Surface traps at the channel
  - Traps within the semiconductor bulk
  - Charge (ions) drifting within the insulator

$$\Delta V_T(t) = \Delta V_T(\infty) \left( 1 - \exp\left(-\frac{t}{\tau}\right)^m \right)$$

Empirical voltage drift expression:  
Stretched exponential

$m = T/T_0$  for exponential trap distribution given by:

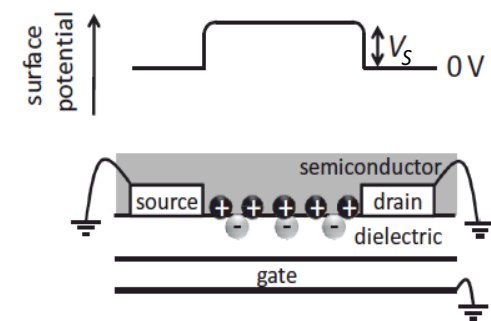
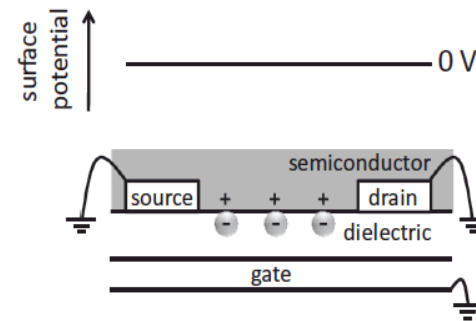
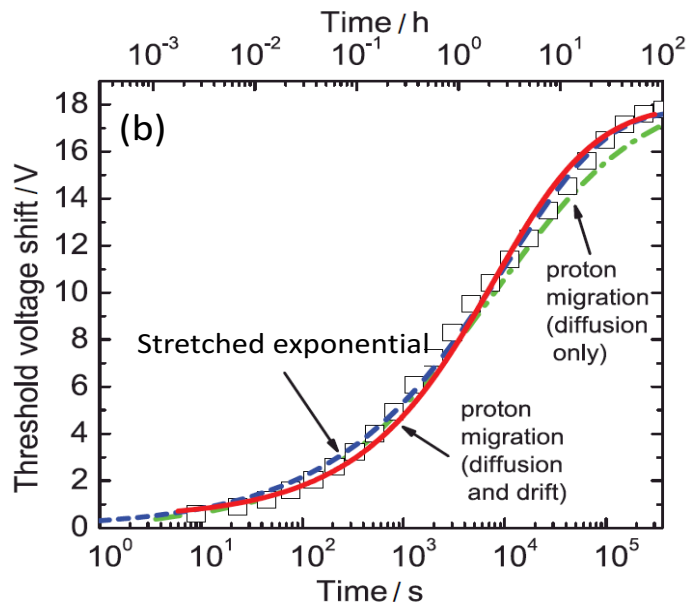
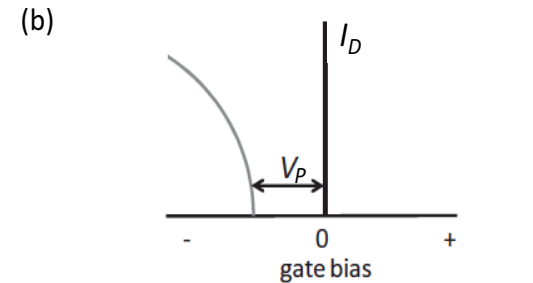
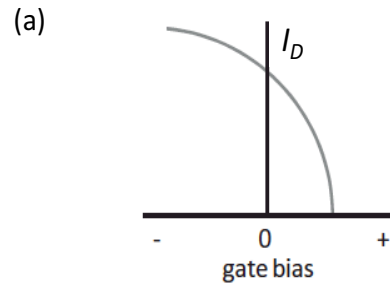
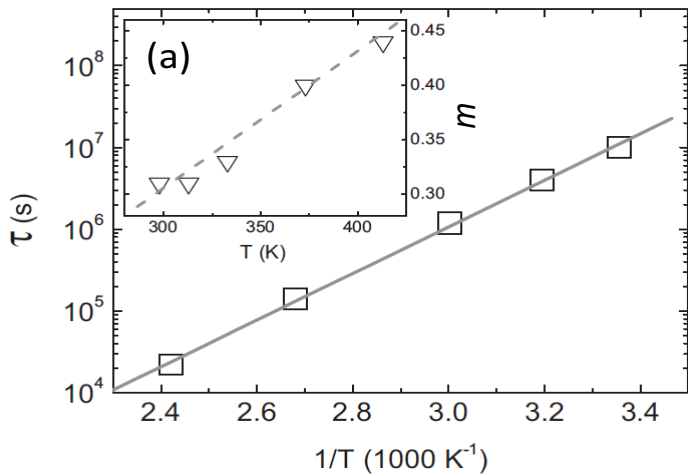
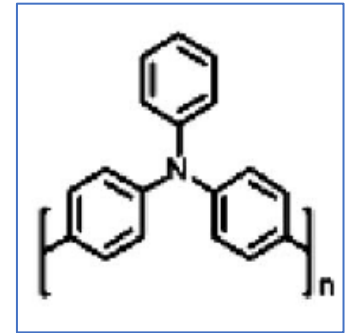
$$h_{tr}(E) = h_{tr0} \exp(-E/E_T)$$

⇒ Time constant for drift

$$\tau = (2\pi\nu)^{-1} \exp(E_T/k_B T)$$

Drift occurs over an extended time, and is thermally activated

# Example: Poly(triarylamine)

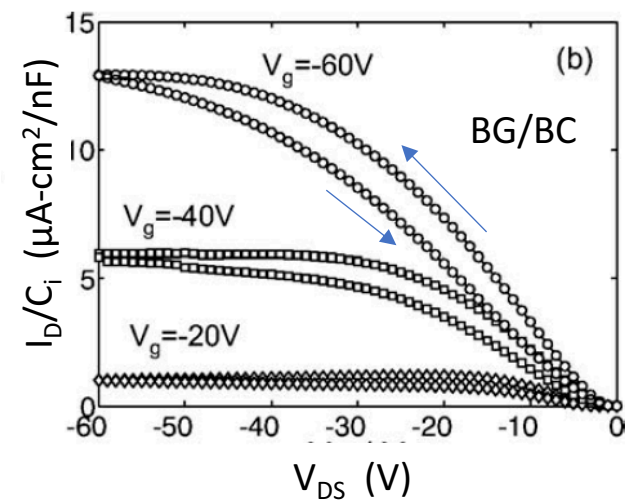
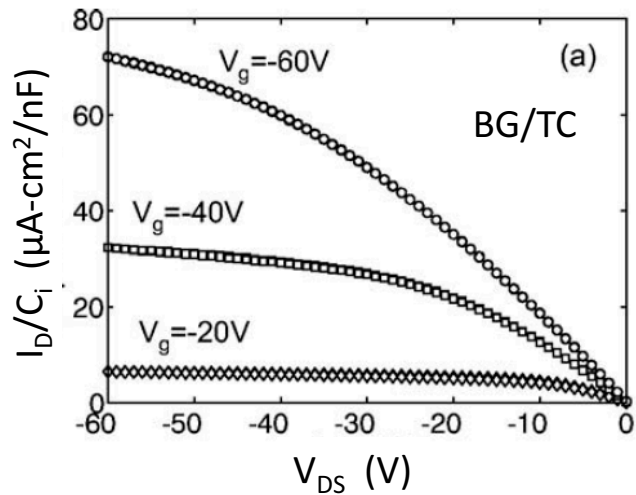


- + mobile positive charge
- ⊕ immobile positive charge
- ⊖ immobile negative charge

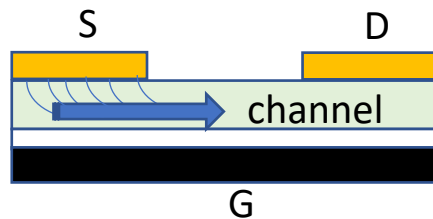
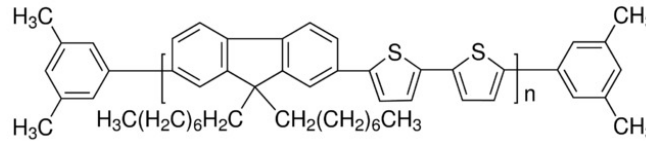
Water is the main problem: Proton generation onics  
Stephen K. Porrest



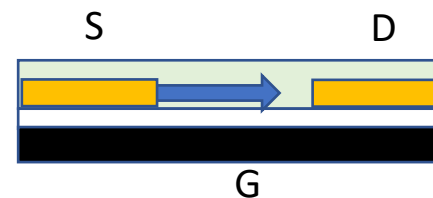
# Hysteresis: Another failure mode



p-channel F8T2 transistors



BG/TC: Large contact area to channel  
Current drawn from contact surface (arrow)

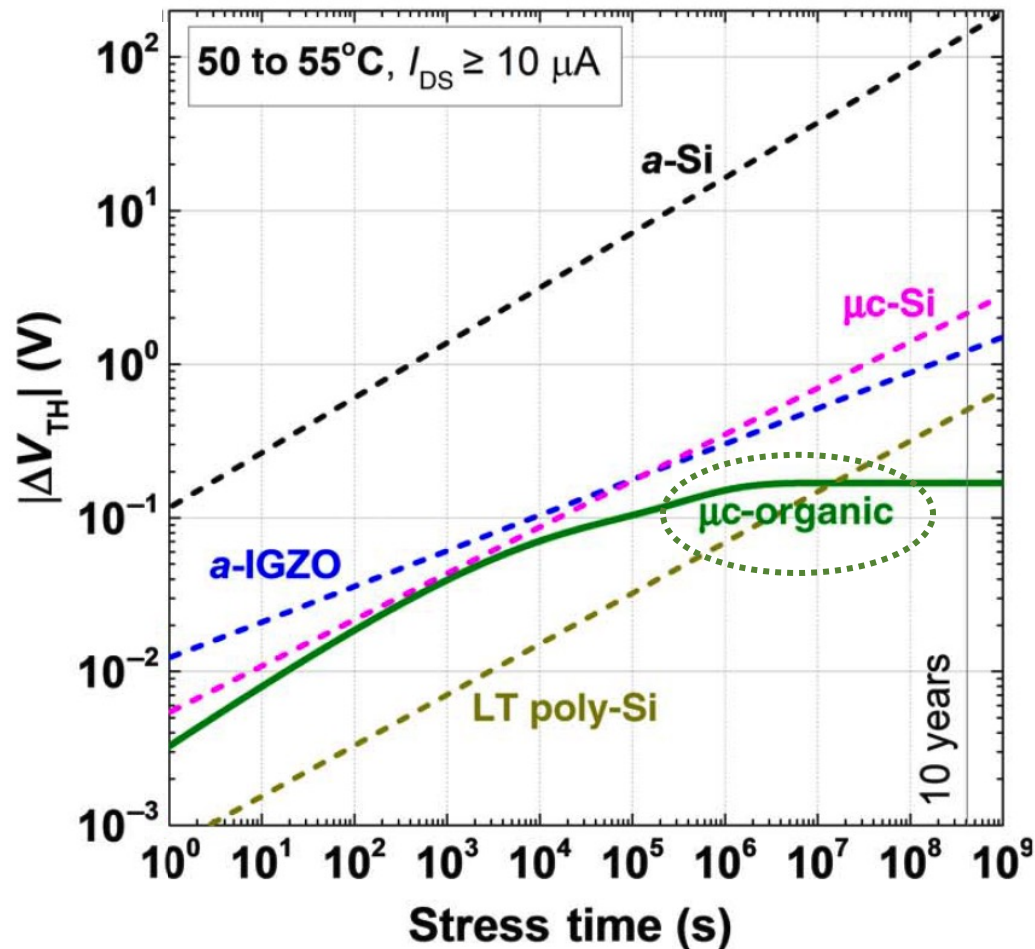


BG/BC: Small (edge) contact to channel  
Current drawn from contact edge (arrow)

## Drain contact trapping

Contact only via edge of the electrodes increases the current density, resulting in defect formation and charge trapping. This induces changes in  $V_T$  and  $I_{DS}$ , depending on sweep direction (arrows)

# Comparison of TFT Reliabilities



Jia, et al. Science Adv. 4, eaao1705, (2018)

Caveats (and there are many):

- Devices from different labs may be based on different standards and conditions
- Device selection not necessarily based on same characteristics
- Performance can vary over a wide range in any technology

# Applications must exploit advantages, and cannot be vulnerable to disadvantages

To review....

- PROs

- Flexible, conformable, ultralight
- Can be made over very large areas
- Suitable for large scale R2R manufacture

- CONs

- Cannot source large currents
- Characteristics drift over long periods in operation
- Limited bandwidth ( $\leq 1$  MHz in many cases)

# Voltage driven display backplanes

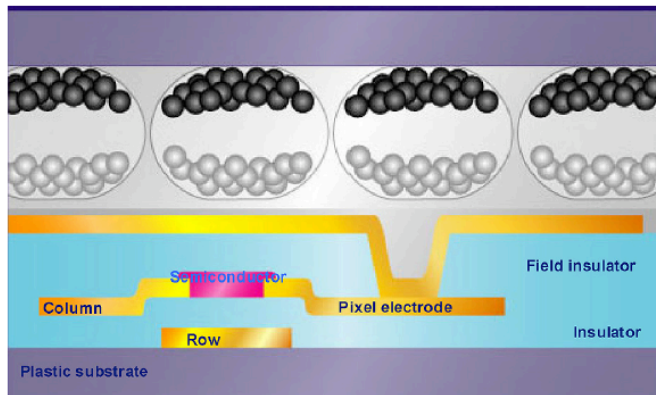
- Electrophoretic displays



320 x 240 QVGA display

Display pixels are voltage (not current) driven

QVGA=quarter video graphics array



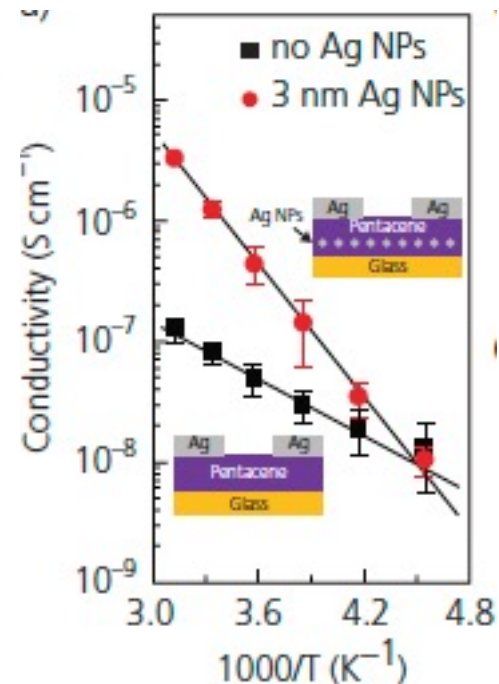
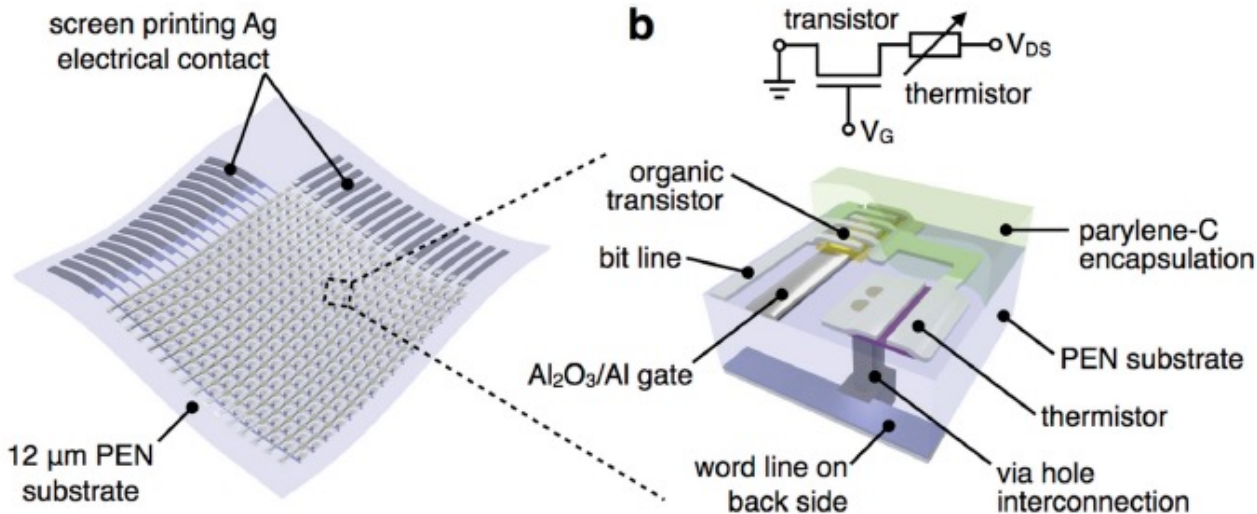
Organic Electronics  
Stephen R. Forrest

G. Gelinck *et al* *J. Soc. Info. Display*, **14**,113, 2006<sub>24</sub>



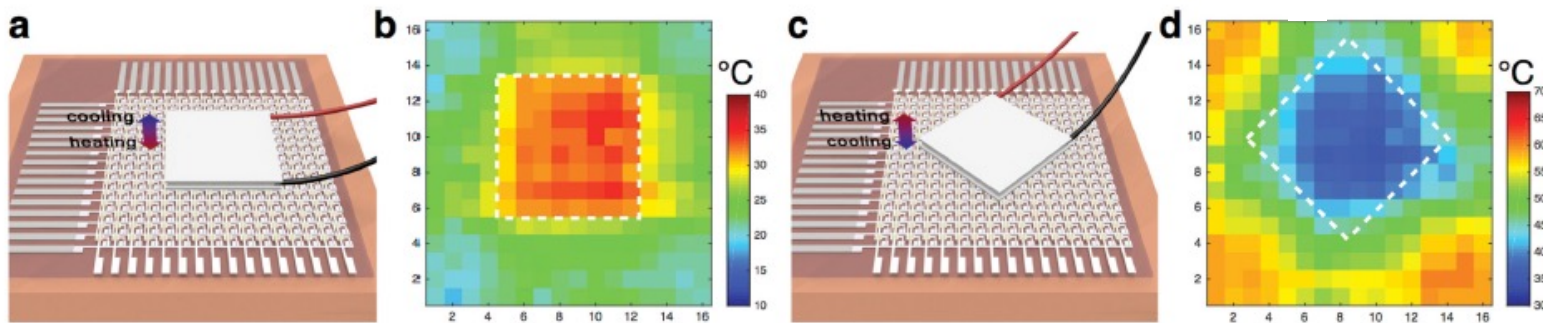


# Thermal Position Sensing



Array used for detecting position of thermal source

Sensing element: channel resistance with a Ag NP layer



# Chemical sensing

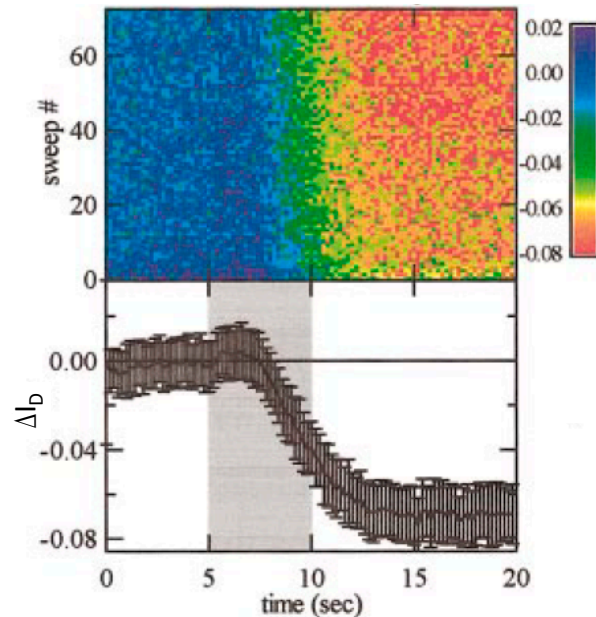
- OTFTs have demonstrated voltage drifts due to water.
- Are there other analytes that can be sensed?
- Sensor attributes
  - Fast
  - Sensitive to small doses
  - Reversible
  - Specific

$\alpha$ -6T transistor

Analyte: 1-hexanol

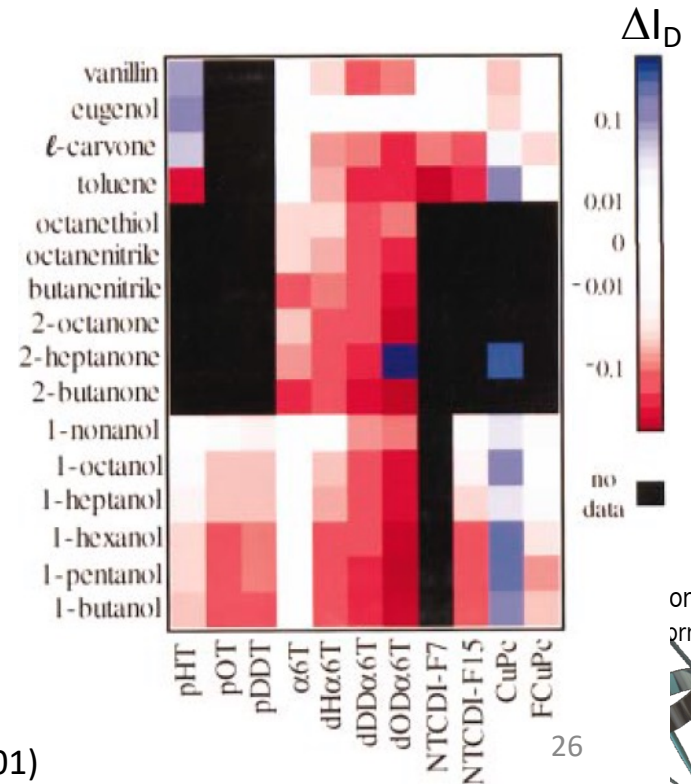
Exposure: 5 s

Recovery: 1 min



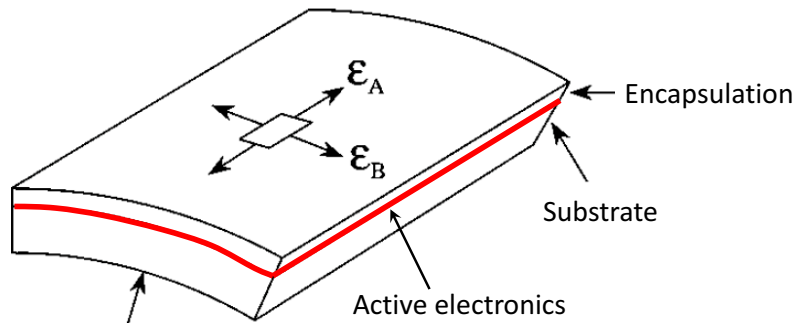
16 analytes

11 transistor channel mater.



# Bendable Electronics

Placing active electronics at the neutral strain point  
 ⇒ minimal stress to circuits on bending even over sharp angles

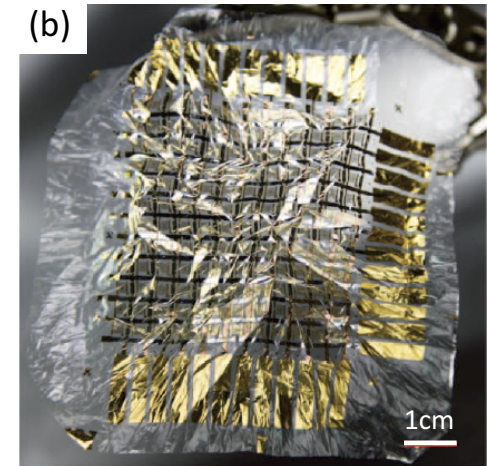
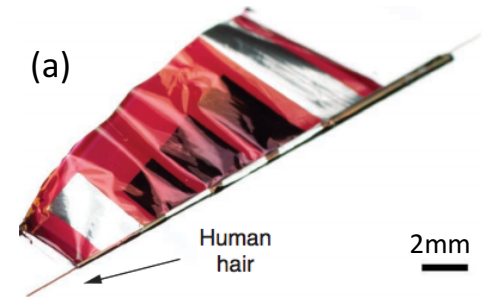


Neutral strain:  $\frac{d_{sub}}{d_e} = \sqrt{\frac{Y_e}{Y_{sub}}}$

Y = Young's modulus (measure of material stiffness)

$$Y = \frac{FL_0}{A\Delta L}$$

$F$  = force to extend solid  
 $L_0$  = original length  
 $\Delta L$  = length change  
 $A$  = cross sectional area perpendicular to  $F$

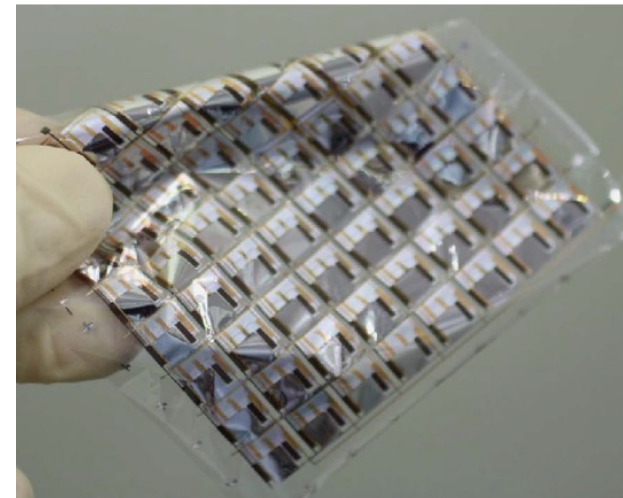
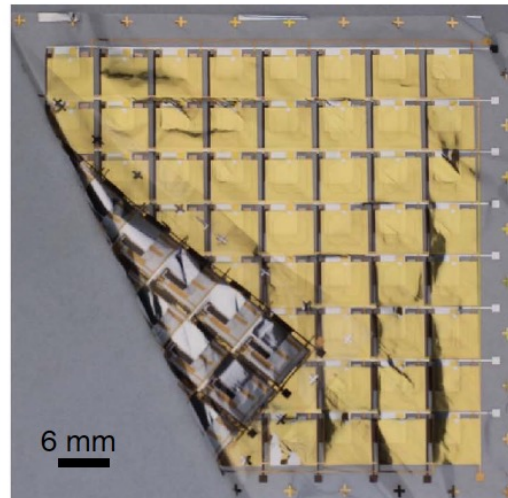
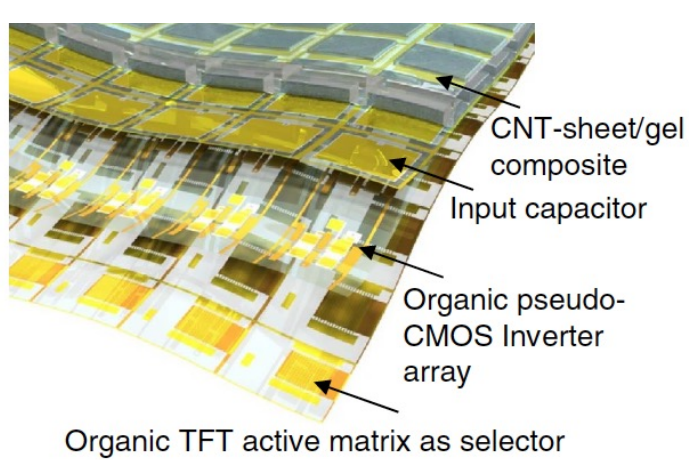


12x12 array of tactile pixels

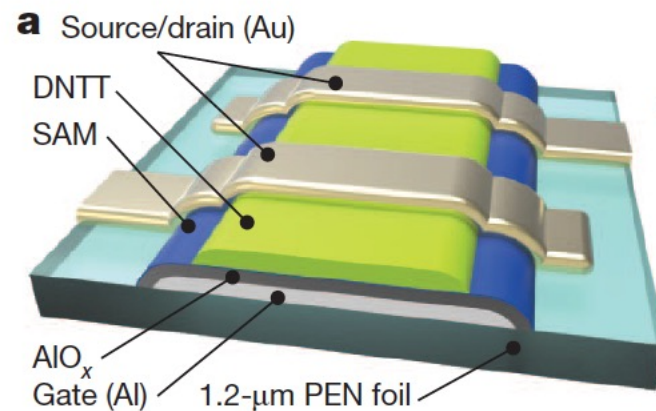
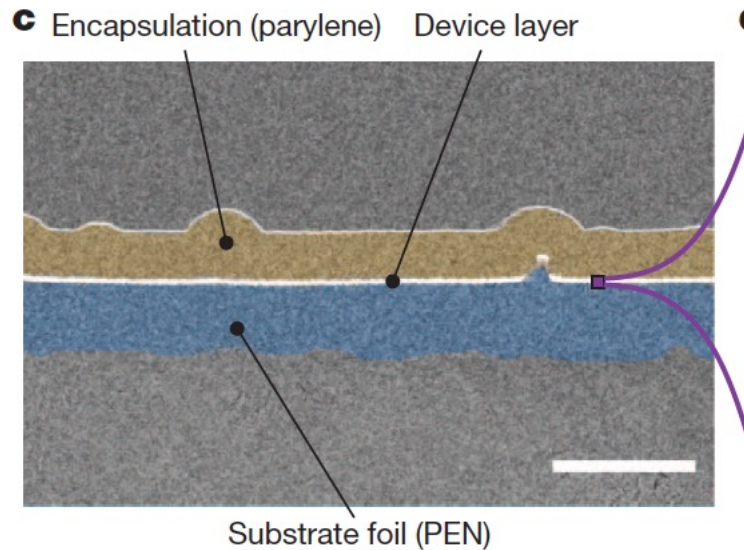
Organic Electronics  
 R. Forrest



# “Imperceptible” Electronics

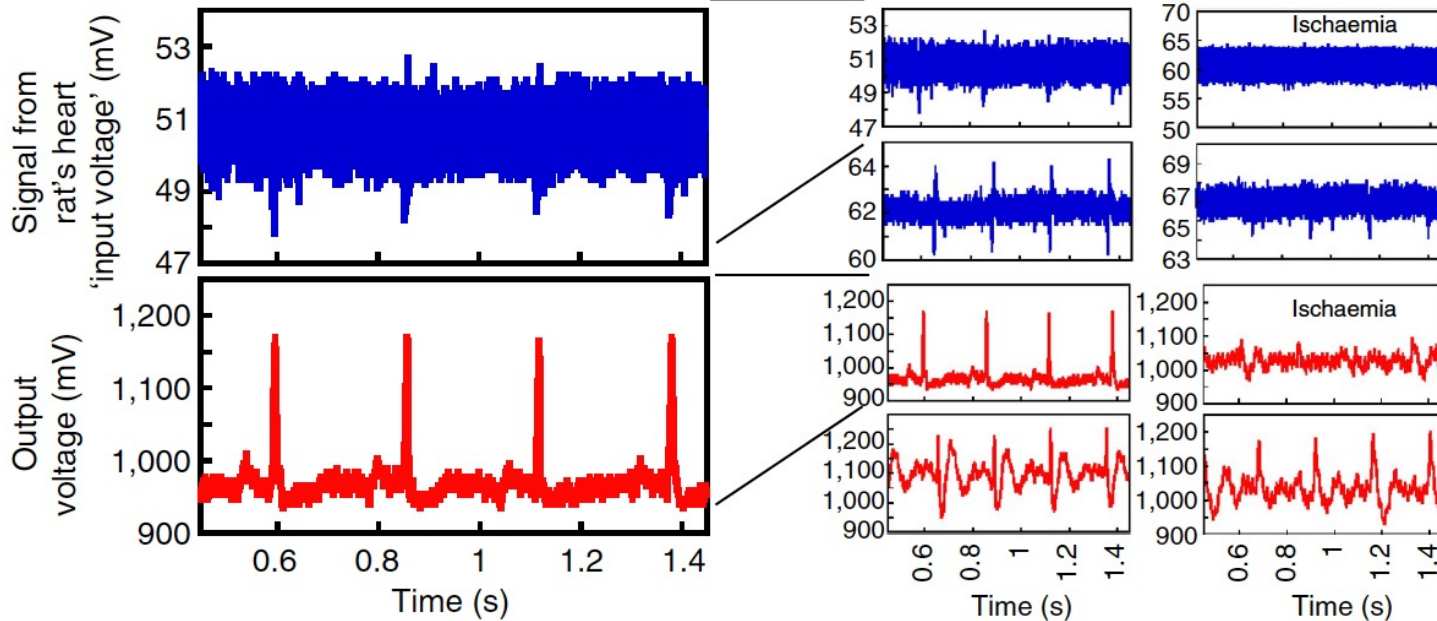
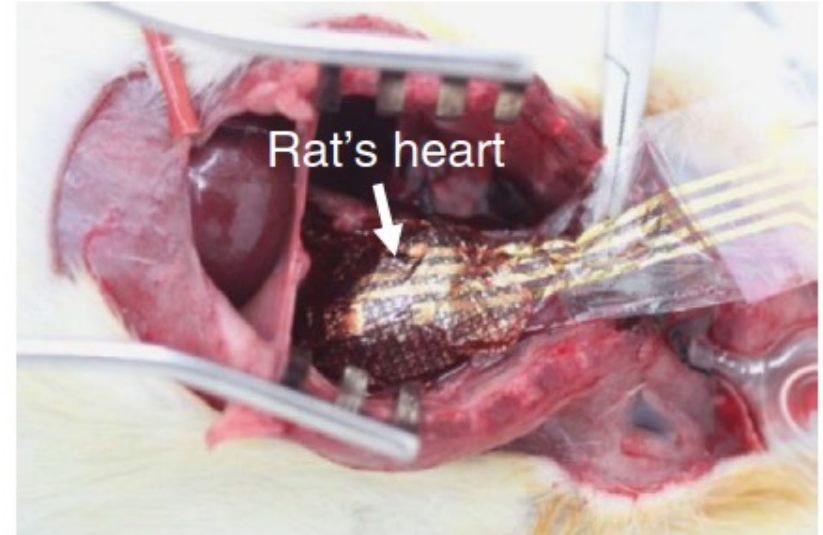
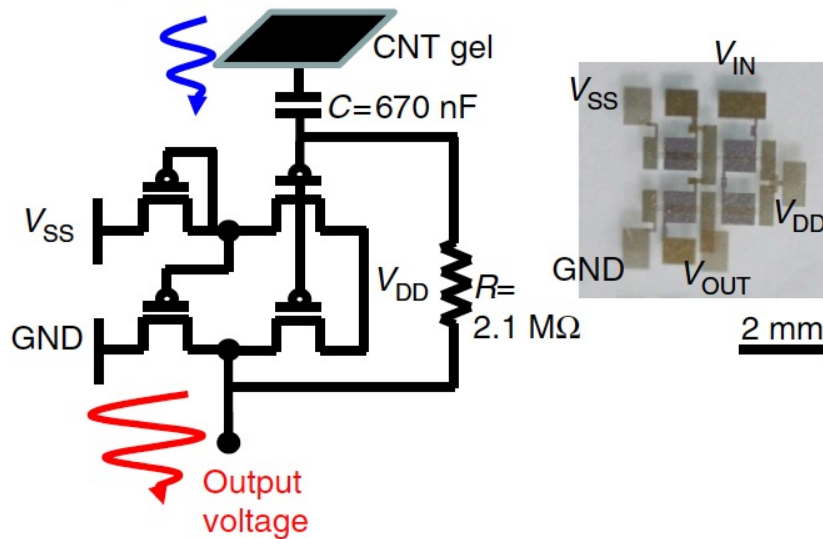


Substrates are 1  $\mu\text{m}$  thick!



# In Vivo Cardiac Monitoring

Input biosignal from the heart



# What we learned

- OTFTs have made extraordinary progress since their first demonstration in 1986
- Their properties can be modified through chemical design
- Morphology is key to high performance
- Very small gate transistors are common in BG/TC configurations
- Very large circuits demonstrated (100's of transistors)
- Reliability depends on exposure to contaminants
- Most promising applications in sensing and medicine
- But....there is no “killer app” yet identified that can drive this technology to a commercial success